WAFER DRYING APPARATUS

ABSTRACT

A wafer drying apparatus is disclosed. The disclosed wafer drying apparatus includes a processing tank, a liquid supplying device, a liquid draining device at the bottom of the processing tank, a liquid draining device at the one side of the processing tank, an exhausting device at the one side of the processing tank, a wafer holding device which includes a supporting element, a wafer carrier, and a driving device to drive the supporting element; and a cover which can receive at least one wafer inside and at least one holding device which can releasably hold the wafer.

Fig. 1